

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q67625

SMILANSKY, Zeev, et al.

Appln. No.: 10/003,347

Group Art Unit: 2623

Confirmation No.: 6579

Examiner: Vikkram Bali

Filed: December 06, 2001

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For: A PIXEL BASED MACHINE FOR PATTERENED WAFERS

FEB 2 5 2003

AMENDMENT UNDER 37 C.F.R. § 1.111

Technology Center 2600

Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Office Action dated November 19, 2002, within the shortened statutory period extended by one month, please amend the above-identified application as follows:

## IN THE CLAIMS:

## Please add the following new claims:

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26. (New)

A method of analyzing the surface of a semiconductor wafer comprising:

illuminating a portion of the surface of the semiconductor wafer with light;

detecting light scattered by the illuminated portion of the surface of said semiconductor wafer as individual pixel signatures;

evaluating said pixel signatures according to a predetermined criterion;

discriminating between valid and at least one of suspect and defective pixels.

27. (New) The methods of claim 26 wherein a plurality of pixels is illuminated and checked concurrently.